--19. A scanning exposure system according to claim 16, wherein the illumination region setting device provides the illumination region which has triangular ends.--

--20. A scanning exposure system according to claim 19, wherein the ends of the illumination region are exposed to an illumination gradient.--

--21. A scanning exposure system according to claim 16, wherein the illumination region setting device includes at least one blind plate for providing the illumination region with a triangular end and at least one end light-shielding blind plate which covers the triangular end of the at least one illumination region.--

--22. A scanning exposure method according to claim 14, wherein the illumination region has a pentagonal or hexagonal shape.--

--23. A scanning exposure method according to claim 14, wherein the size, of the illumination region, in a direction different from the synchronous moving direction of the substrate is changed by reversing a direction of illumination during the synchronous movement.--

--24. A scanning exposure method according to claim 14, wherein an adjacent pattern is exposed so as to be partially overlapped with the pattern.--

--25. A scanning exposure method according to claim 24, wherein an overlapping part which is partially overlapped with the pattern is formed in a zigzag pattern.--

--26. A scanning exposure method according to claim 24, wherein the adjacent pattern, which is adjacent to the pattern in an orthogonal direction to the synchronous moving direction, is exposed so as to be partially overlapped with the pattern.--

--27. A scanning exposure method according to claim 24, wherein the adjacent pattern, which is adjacent to the pattern in the synchronous moving direction, is exposed so as to be partially overlapped with the pattern.--